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(54) Title: EXTREME ULTRAVIOLET MASK ABSORBER MATERIALS

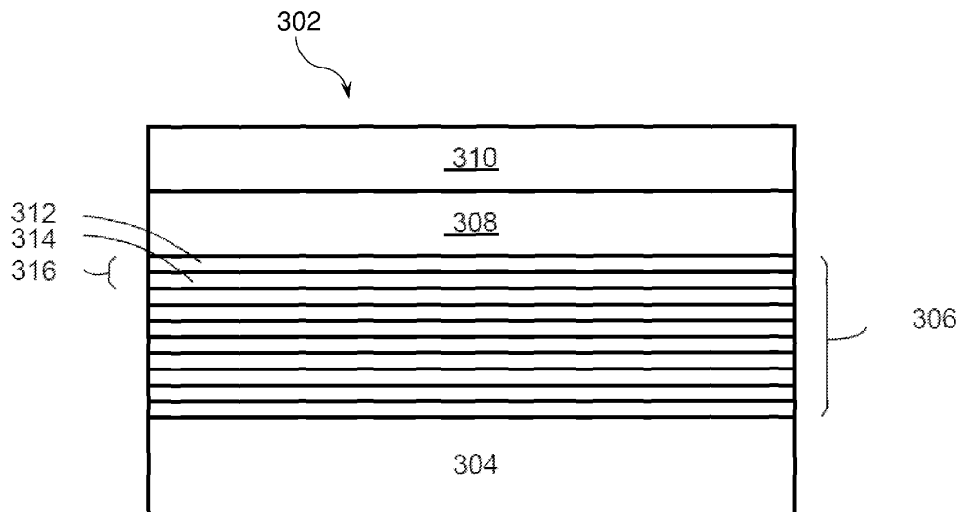


FIG. 4

(57) Abstract: Extreme ultraviolet (EUV) mask blanks, methods for their manufacture and production systems therefor are disclosed. The EUV mask blanks comprise a substrate; a multilayer stack of reflective layers on the substrate; and an absorber layer comprising tantalum and iridium or ruthenium and antimony.

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